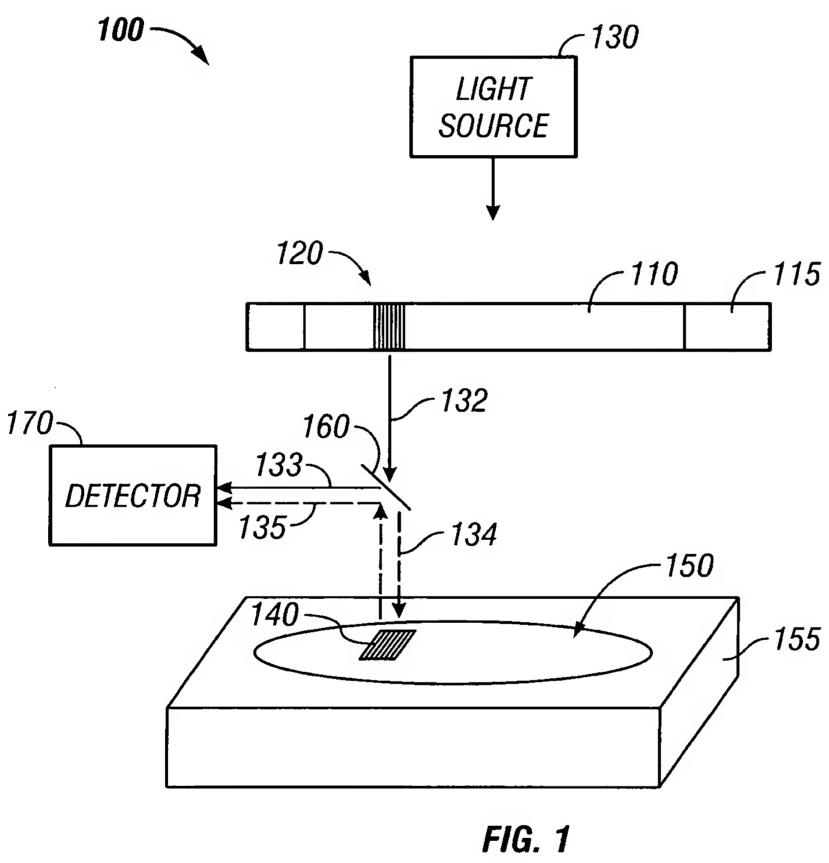
*1/5* 





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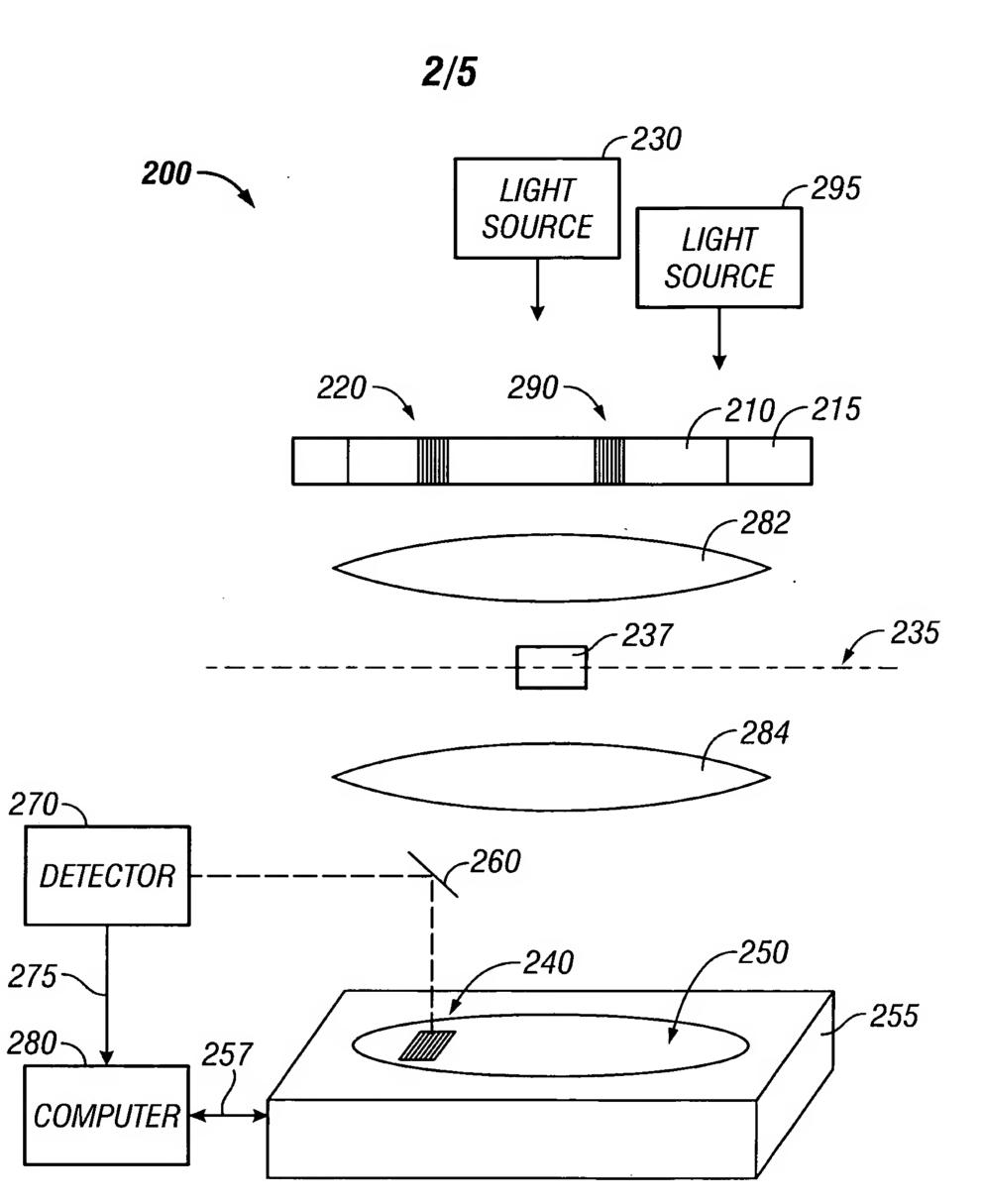
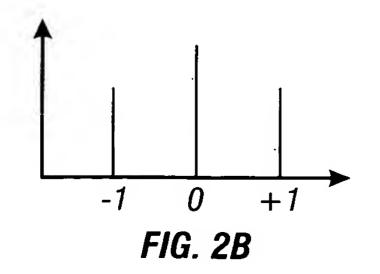
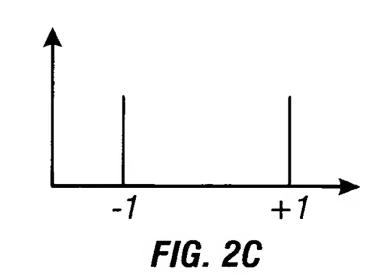
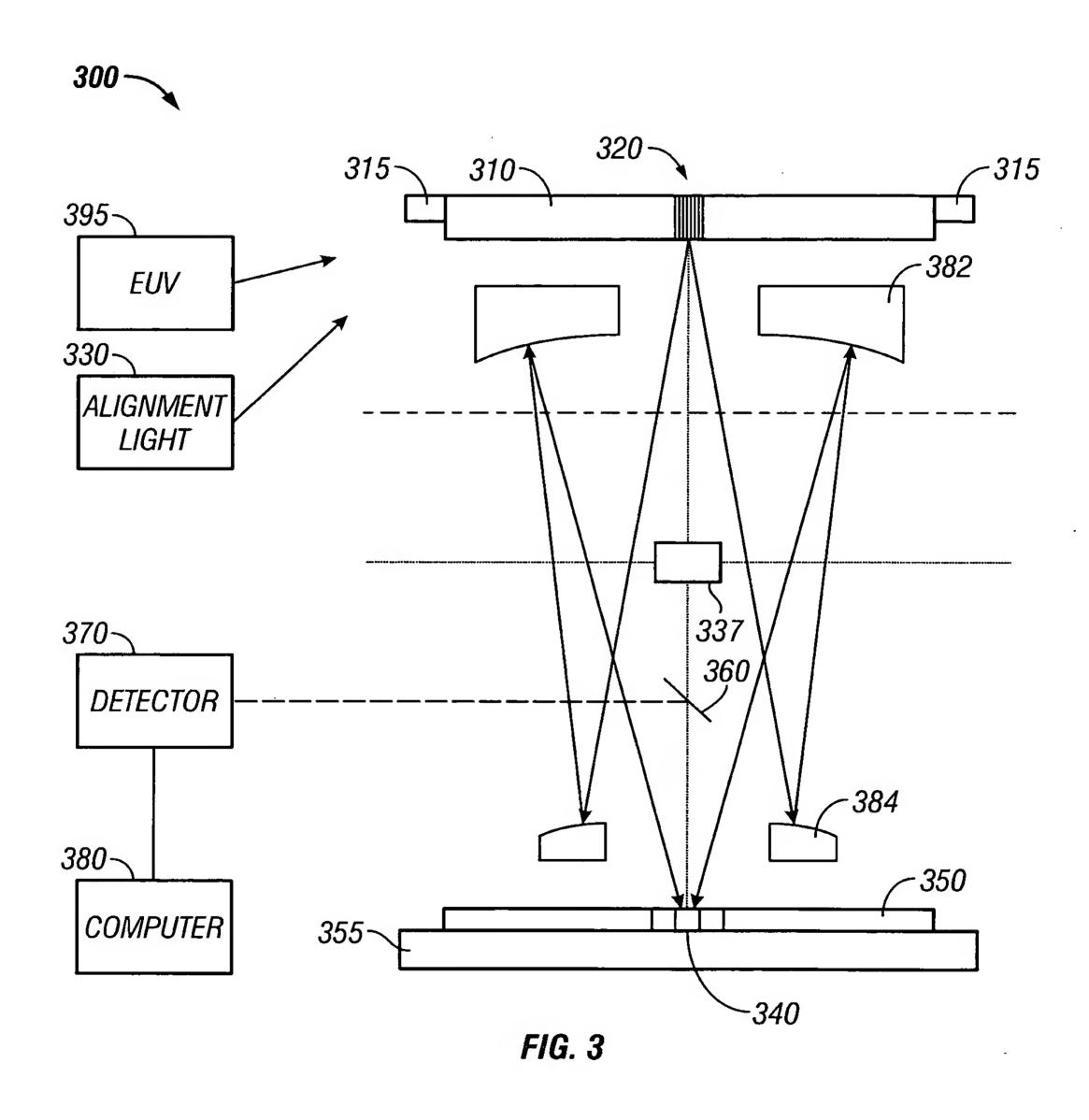


FIG. 2A





*3/5* 





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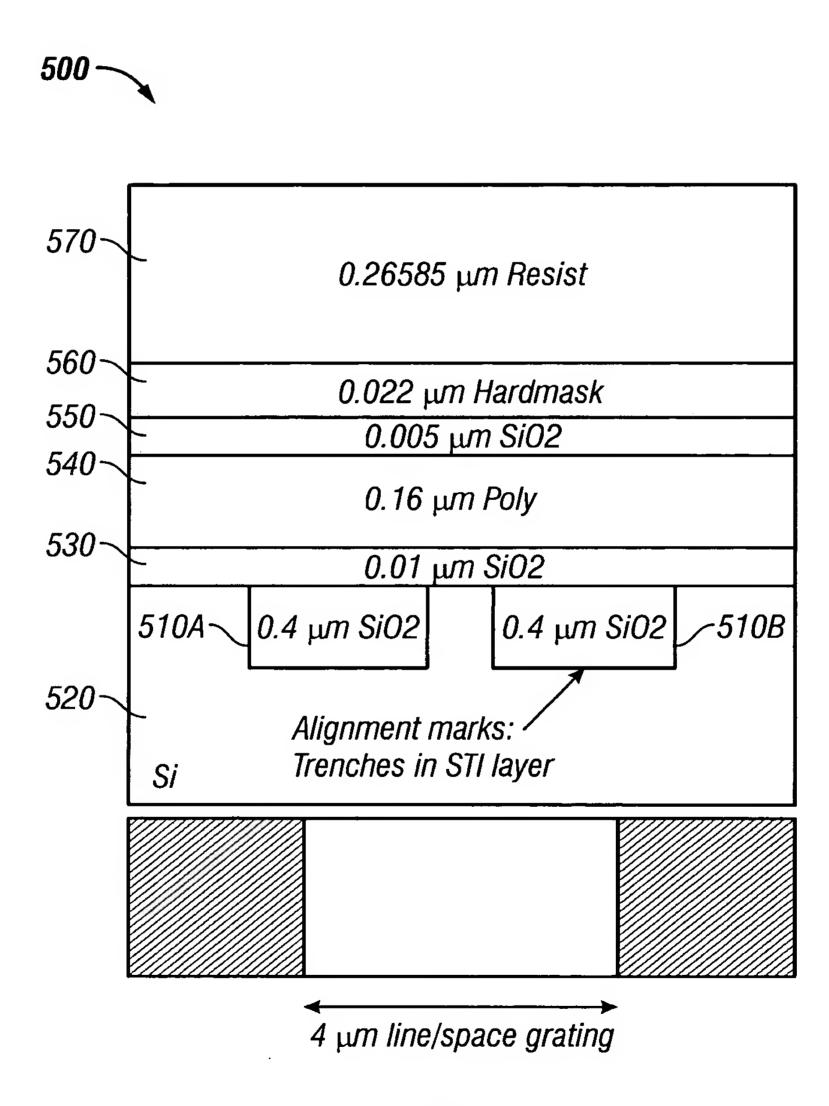
4/5

*400* · 405 POSITION IMAGING PLATE IN HOLDER 410 POSITION WAFER ON WAFER STAGE 415 TRANSMIT LIGHT THROUGH ALIGNMENT GRATING ON **IMAGING PLATE** 420 BLOCK CENTRAL MAXIMUM AT PUPIL PLANE 425 ALLOW FIRST ORDER MAXIMA TO PASS AT PUPIL PLANE 430 REFLECT A PORTION OF INCIDENT LIGHT FROM ALIGNMENT PATTERN ON WAFER 435 DETECT AT LEAST SOME OF THE REFLECTED LIGHT 440 VARY POSITION OF WAFER WITH RESPECT TO RETICLE 445 **DETERMINE ALIGNMENT** CHARACTERISTIC OF POSITIONS 450 **DETERMINE AN ALIGNMENT POSITION** 

FIG. 4



*5/5* 



*FIG.* 5